LETI ALTERNATIVE LITHOGRAPHY WORKSHOP

MARRIOT HOTEL, SAN JOSE
MARCH 1ST, 5 P.M.

Leti ecosystem
> Laurent Pain, Patterning program manager, Leti

Accelerated innovation: a strategic collaboration with Leti
> Olivier Vatel, Senior Vice President, CTO and Corporate Director, SCREEN Semiconductor Solutions Co. Ltd.

Mapper technology: ramping up the pace of industrialization
> Marco Wieland, Co-founder and CTO, Mapper

FLX performances in Leti’s pilot line
> Cyrille Laviron, Lithography manager, Leti

DSA of block copolymers: materials
> Christophe Navarro, DSA material product development manager, Arkema

DSA of block copolymers: integration
> Raluca Tiron, DSA program manager, Leti

EVG SmartNIL technology for patterning requirements in More than Moore applications
> Martin Eibelhuber,
  Business development manager, EVG

INSPIRE: Leti NIL assessment platform
> Hubert Teyssedre,
  NIL program manager, Leti

Leti “Lithopole”
> Laurent Pain,
  Patterning program manager, Leti

Future isn’t what it is used to be
> Yan Borodovskiy,
  SPIE fellow & Intel fellow
Leti, a technology research institute at CEA Tech, is a global leader in miniaturization technologies enabling smart, energy-efficient and secure solutions for industry. Founded in 1967, Leti pioneers micro- and nanotechnologies, tailoring differentiating applicable solutions for global companies, SMEs and startups. Leti tackles critical challenges such as healthcare, energy and ICTs. From sensors to data processing and computing solutions, Leti’s multidisciplinary teams deliver solid expertise, leveraging world-class pre-industrialization facilities. With a staff of more than 1,900, a portfolio of 2,700 patents, 91,500 sq. ft. of cleanroom space and a clear IP policy, the institute is based in Grenoble, France, and has offices in Silicon Valley and Tokyo. Leti has launched 60 startups and is a member of the Carnot Institutes network.

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Learn more about Leti:
www.leti-cea.com